# Analog Electronic Circuits (EC2.103): Assignment-3

(Instructor: Prof. Zia Abbas, CVEST, IIIT Hyderabad)

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#### **Instructions:**

- 1. Submit your assignment as a single pdf (Name RollNo.pdf) at moodle on or before the due date
- 2. Hand-written/typed (notion/latex/word) submissions are allowed
- 3. Report should be self explanatory and must carry complete solution Answers with schematics, SPICE directives, annotated waveforms, inference/discussion on results as asked in the questions.
- 4. Use the TSMC\_180nm.txt file for the MOSFET models.
- 5. Post your queries on moodle. Discussions are highly encouraged on moodle
- 6. Any form of copying/cheating will result in immediate F grade

### 1. Region of Operation

- (1.1) List the different regions of operation for NMOS and PMOS transistors. For each region, specify the conditions on terminal voltages that define the region. Additionally, provide the corresponding drain current equations in each region.
- (1.2) For the following configurations in Fig.1, find out the operating region, the current flowing through the MOSFET and justify your answer with proper equations. (You can take  $\mu_n C_{OX} = 300 \mu A/V^2$  and the aspect ratio of the MOSFET to be  $\frac{2\mu}{l\mu}$ ):
- (1.3) Answer the following questions referring to Fig.2.
  - (a) Show that for the PMOS to operate in saturation region,

$$I \times R \le |V_{thp}|$$

- (b) If the transistor is specified to have  $|V_{thp}|=1V$  and  $K_p=0.2mA/V^2$  and for  $I_d=0.1mA$ , find the voltages  $V_{SD}$  and  $V_{SG}$  for the following values of resistance: (i)  $0\Omega$  (ii)  $10k\Omega$  (iii)  $100k\Omega$
- (1.4) For the circuit in FIg.3, find the following
  - (a) Region of Operation
  - (b) Biasing current and transconductance
  - (c) Range and limit of gate voltage for the MOSFET to remain in saturation

(Consider 
$$\mu_n C_{OX} = 100 \mu A/V^2$$
,  $V_{thn} = 0.5 V$  and  $\frac{W}{L} = \frac{1.8 \mu}{0.18 \mu}$ )

## 2. Small Signal Model and Impedances

- (2.1) Draw the complete small signal model of NMOS and PMOS(include the capacitances as well).
- (2.2) For the configurations of MOSFET shown in FIg.4, find the impedance as asked (assume that the MOSFETs are in saturation in all the scenarios):

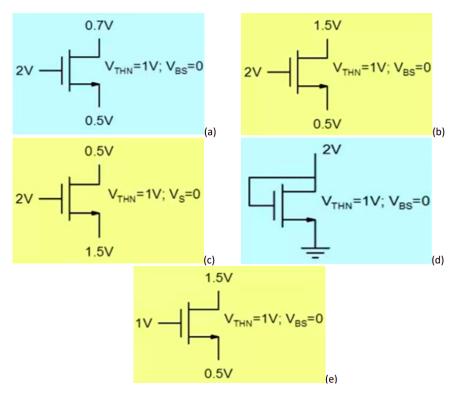


Figure 1: Figure related to 1.2

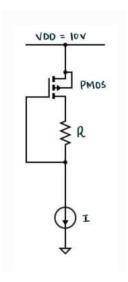


Figure 2: Figure related to 1.3

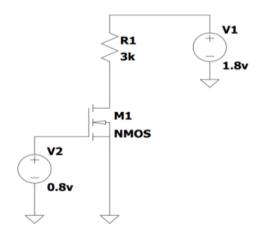


Figure 3: Figure related to 1.4

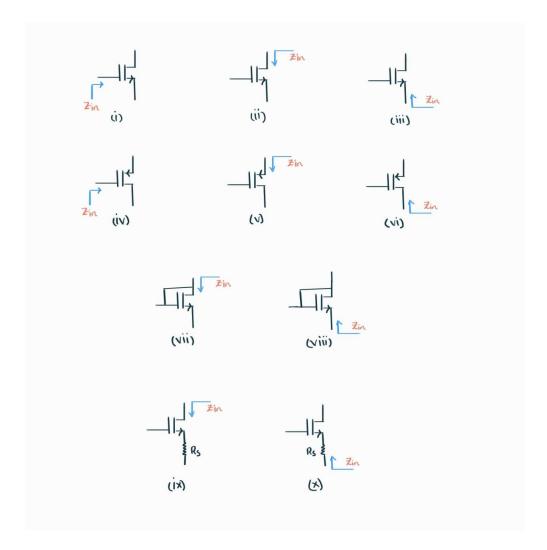


Figure 4: Figure related to 2.2

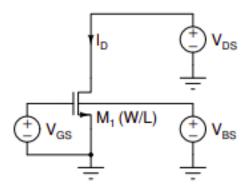


Figure 5: Figure related to 3.1

### 3. LTSpice Simulations: MOSFET Characterization

- (3.1) As shown in Fig.5, plot  $I_D$  vs  $V_{GS}$  for an NMOS transistor having  $\frac{W}{L} = \frac{1.8\mu}{0.18\mu}$  by sweeping  $V_{DS}$  from 0 to 1.8V with a step of 0.01V and sweeping  $V_{GS}$  from 0 to 1.8V with a step of 0.3V. Assume  $V_{BS} = 0V$ . (Hint: Use NMOS4 from library, edit and change model name to CMOSN, enter W,L,drain/source area (AD/AS), drain/source perimeter (PD/PS) as follows:  $AS = \{5*width_N*LAMBDA\}$ ,  $PS = \{10*LAMBDA + 2*wdith_N\}$ ,  $AD = \{5*width_N*LAMBDA\}$  and  $AD = \{10*LAMBDA + 2*wdith_N\}$  where  $AD = \{10*LAMBDA\}$  and  $AD = \{10*LAMBDA\}$  are  $AD = \{10*LAMBDA\}$ .
- (3.2) Plot  $I_D$  vs  $V_{GS}$  for  $\frac{1.8\mu}{0.18\mu}$  NMOS transistor for  $V_{DS} = 50mV$  and  $V_{BS} = 0V$ .
  - (a) Estimate the technology parameter  $\mu_n C_{OX}$  and threshold voltage  $V_{th}$  from the graph for  $V_{DS} = 50 mV$
  - (b) Plot  $I_D$  vs  $V_{GS}$  for  $V_{DS} = 1.8V$  and extract the threshold voltage. Compare the obtained  $V_{th}$  with  $V_{DS} = 50mV$  case. Do you observe any difference in the values obtained in the two cases? If yes, explain why. (*Hint*: *DIBL*).
- (3.3) From the simple MOS models discussed, find out  $V_{th}$  for NMOS and PMOS devices ( $\frac{W}{L} = \frac{1.8\mu}{0.18\mu}$  with the help of  $I_D$  vs  $V_{GS}$  simulations for
  - (a) Body to source voltage,  $V_{BS} = 0V$
  - (b) Body to source voltage,  $V_{BS} = 900mV$
  - (c) Body to source voltage,  $V_{BS} = -900mV$

Overlay the three plots . Do you observe any difference in  $V_{th}$  for the three cases? Briefly discuss.

(**Hint**:  $I_D$  vs  $V_{GS}$  simulation with  $V_{BS}$  list, body effect. For PMOS based simulations, use PMOS4 component and use model name: CMOSP, define AS/AD/PS/PD as mentioned earlier.)